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RECIPE DESIGNER 7

Automatic OES Endpoint Engineering Software: Dry Etch, Cleaning, PECVD

- Give Better Life to Process Engineer!
  - Plasma information is complex...
  - Recipe Designer 7 highlights Endpoint
  - Desktop software: build your recipe out of clean room
- Engineering Toolbox for Plasma analysis
  - Process understanding [Learning Sample(s)]
  - Process development
  - Instant Plasma Elements & by-Products Time Trend view
  - Automatic key Endpoint wavelength(s) extraction
- Production Endpoint Recipe
  - Semi-Automatic Endpoint Recipe creation
  - Endpoint validation [Tests sample(s)]

And more: Reprocessing, Signal Treatment, Statistics, Multi-Runs Viewer

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Recipe Designer 7 Software

With Recipe Designer 7 (RD7) Evolution, OES Endpoint and Plasma Monitoring is made easy!

- Dedicated to Process Engineer to develop and stabilize processes
- Unique Stand-alone Mathematical Software to plug in high-grade Real-time Sigma_P software within EV-140 products
- EV-140 already contains full package for:
  - R&D Plasma Monitoring
  - Production
  - Single chamber & Cluster Tool
  - Automation inside Fab’s, Etching Tools
- NOW, with Recipe Designer 7, EV-140 contains full package for IMMEDIATE ENGINEERING and PROCESS DEVELOPMENT:
  - Quick Highlight of relevant wavelengths or species kinetics
  - (quite) Automatic creation of Endpoint and Monitoring recipes
  - Spectra import from Sigma_P & Endpoint recipe export to Sigma_P
- Developed with new technologies. Win 7 compliant

Plasma Information is complex, RD7 makes it clear!

Immediate relevant Elements/Wavelengths time trend view
RD7 Flow to go from spectra to relevant process wavelengths

6 steps!

1. Create Project
2. Add runs in Database
3. Visualize runs
   - Spectra
   - Wavelengths
   - Elements
4. (Auto.) Classify Wavelengths
5. (Auto.) Find Rupture points
   - Up Slope
   - Down Slope
6. Lock Endpoint detection rules
   - Export recipe to Sigma_P

One Click actions!

Average Rupture Wavelengths
For several samples

End point

Rupture intensity

Validation

- Wafer to wafer
- Lot to lot
- Ch. to chamber
- Tool to tool

RD7 is compatible with:

- previous products like PlasmaScope, DigiCPM, DigiCPM_J, MultiCPM
- EV-140 C, EV1000
- Other spectra formats on demand

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